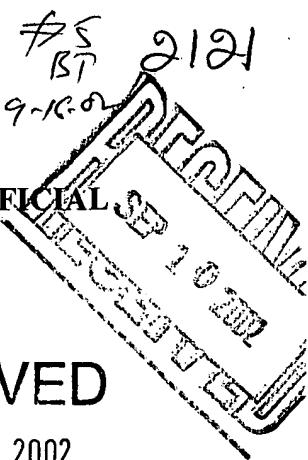




Docket No. 4066 D1/Consilium/DV



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
John F. ARACKAPARAMBIL et al. :
Serial No. 10/084,092 : Group Art Unit: 2121
Filed: February 28, 2002 : Examiner:
For: COMPUTER INTEGRATED MANUFACTURING TECHNIQUES

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INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of the references listed on pages 1 and 2 of Form PTO-1449 are submitted herewith.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

The references listed on Sheet Nos. 4 through 6 of Form PTO-1449 were cited by or submitted to the U.S. Patent and Trademark Office in parent application Serial No. 09/363,966, filed July 29, 1999, which is relied upon for an earlier filing date under 35 USC § 120. Copies of these references are not attached under 37 CFR 1.98(d).

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

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10/084,092APPLICANT
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February 28, 2002GROUP
2121

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						Yes No
	2,050,247	08/29/91	Canada			X
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	2,194,855	08/29/91	Canada			X
	05-151231	06/18/93	Japan			X
	05-216896	08/27/93	Japan			X
	05-266029	10/15/93	Japan			X
	06-110894	04/22/94	Japan			X
	06-176994	06/24/94	Japan			X
	06-252236	09/09/94	Japan			X
	06-260380	09/16/94	Japan			X
	1072967A3	11/21/01	Europe			X

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EXAMINER	DATE CONSIDERED
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APPLICANT

John F. ARACKAPARAMBIL et al.

FILING DATE

February 28, 2002

GROUP

2121

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						Yes	No
	01-283934	11/15/89	Japan			X	
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GROUP
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